

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		#9	Docket No. AMAT/5192/ISM/COR E MCVD/SB	Serial No. 09/776,329
INFORMATION DISCLOSURE STATEMENT BY APPLICANT			Applicant Suetter, et al.	Confirmation No.: 9575
(Use several sheets if necessary)			Filing Date February 2, 2001	Group 2812
Examiner		Unknown		

## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1						
	A2						
	A3						
	A4						
	A5						
	A6						
	A7						
	A8						
	A9						
	A10						
	A11						
	A12						

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
TMT	C1	Rossnagel, S.M., et al., "Plasma-enhanced atomic layer deposition of Ta and Ti for interconnect diffusion barriers," J. Vac. Sci. Technol. B 18(4), Jul/Aug 2000
TMT	C2	Partial Search Report (Annex to Form PCT/ISA/206), dated October 25, 2002 for PCT/US02/02654
	C3	

Examiner	T. M. Thomas	Date Considered	07/09/03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.